

AMENDMENTS TO THE SPECIFICATION

On page 6, lines 16 to 21:

Turning to FIG. 4, an oxide film ~~114~~ 113 for a spacer is deposited on the entire structure. It is preferable that a high temperature oxide (HTO) film using SiH_2Cl_2 (dichlorosilane; DCS) is used as the oxide film ~~114~~ 113 for the spacer. Further, it is preferred that the oxide film ~~114~~ 113 for the spacer is deposited in a thickness of about $400 \sim 1000\text{\AA}$ at a temperature of about $680 \sim 730^\circ\text{C}$.